ABSTRACT:

Method of manufacturing a thin-film magnetic head, and magnetic head obtainable by means of said method.

Method of manufacturing a magnetoresistive magnetic head in which a first insulation layer (5) of a non-magnetic material is formed on a support face (3a), on which insulation layer a soft-magnetic layer having an upper face remote from the first insulation layer is formed by deposition of a soft-magnetic material. Subsequently a layer portion is removed for forming the flux-guiding elements (17a, 17b) and an aperture extending between said elements, and non-magnetic material for forming a second insulation layer (18) having an upper face remote from the soft-magnetic layer is deposited on the soft-magnetic layer and in the aperture formed therein, which second insulation layer has such a thickness that, viewed in a direction transverse to the support face, the smallest distance between the support face and the upper face of the second insulation layer is larger than the largest distance between the support face and the upper face of the soft-magnetic layer. Subsequently, a mechanochemical polishing treatment is performed as from the upper face of the second insulation layer for forming a main surface (19) at which magnetoresistive material is subsequently deposited for forming a magnetoresistive element (23).

(Fig. 17)

This Sheet Has Been Replaced

